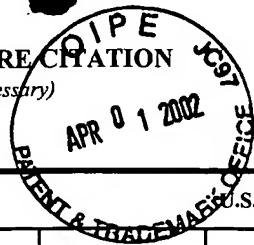


INFORMATION DISCLOSURE CITATION

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Docket Number (Optional)

2002US303

Application Number

10/042,531

Applicant(s)

Takanori Kudo et al

Filing Date

January 9, 2002

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1752

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
EA		4,491,628	01/01/1985	Hiroshi Ito et al			
UB		5,350,660	09/27/1994	Fumiyoshi Urano et al			
EA		5,843,624	12/01/1998	Francis M. Houlihan et al			

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FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
EA		GB 2320718		Great Britain				
		EP 789,278		Europe				
		WO 00/67072		Europe				
EA		WO 00/17712		Europe				

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EA		Hiroshi Ito et al, "Polymer design for 157 nm chemically amplified resists", SPIE Vol. 4345, 2001, pages 273 - 284
EA		Minoru Toriumi, "Resist materials for 157-nm lithography", SPIE Vol. 4345, 2001, pages 371 -- 378

EXAMINER

R Ashton

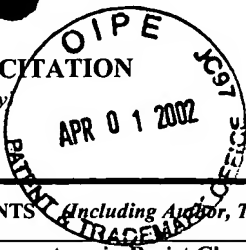
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Przybilla et al, "Hexafluoroacetone in Resist Chemistry: A Versatile New Concept for Materials for Deep UV Lithography", SPIE, Vol.1672, 1992, pg. 500-512

przybilla

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